## Contents

List of Illustrations	ix
List of Tables	ii
1. Basics of Ellipsometry	1
1.1 Physics	7
1.2 Instrumentation	7
1.2.1 Null Ellipsometry	7
1.2.2 Photometric Ellipsometry	9
1.3 Developments in Ellipsometry	12
	14
2. Ellipsometry in Microelectronic Technology	19
2.1 Semiconductor Substrates and Films	19
2.2 Insulating Films	20
	21
3. Error Effects in Ellipsometric Investigations	23
	24
Dir rundom mondere monder in the contract of t	30
3.2.1 Null Ellipsometers	30
3.2.1.1 Error Sources	30
3.2.1.2 Numerical Alignment	36
3.2.2 Rotating Analyzer Ellipsometers	43
3.2.2.1 Intrinsic Accuracy	45
	47
J.D.D.D IInguia. Discourt Gronn-B	51
J.D.D.J I OHOULD WILL INCIDENT	<i>J</i> 1
3.2.2.4 The Influence of the Error Effects Discussed on the	57
Ellipsometric Angles Ψ and Δ	68
5121215	
5.5 Effects of the sample officers.	70
J.J.1 Outditate Reliabling Page 1	70
3.3.2 Interface Layer Between Substrate and Film	72



viii Contents

Appendix A: Design Considerations for a F	High-Speed Rotating
Analyzer Ellipsometer	81
A1 The Optical Assembly	82
A2 Electronic Interface Circuitry	85
A3 The Microcomputer System	86
A3.1 Hardware	86
A3.2 Software	87
References	91
Subject Index	97

Fig. 14:	Angle of incidence determination: Real and imagi- nary parts of the calculated film thickness $d_c$ as functions of the angle of incidence $\alpha_c$ used in the		
Tia 15.	calculations		40
Fig. 15:	of incidence $\alpha_c$ as a function of the actual film		
Fig. 16:	computed at the calculated angle of incidence $\alpha_c$ as		40
Fig. 17:	ter: Relative errors of the DC component, $\Delta I_0$ , and of the normalized AC amplitude, $\Delta e$ , and standard deviation of the phase error $\Delta \Phi$ for $e=1$ as a function of the initial mean intensity $I_{00}$ or of the		42
Fig. 18:	resolution r of the digitized intensity signal Effect of angular encoder orbiting: Error $\Delta e$ of the normalized AC amplitude as a function of the phase modulation depth $\delta$ for one (a) and two (b) signal	• •	46
Fig. 19:	periods processed		49
F1g. 19;	Effect of angular encoder orbiting: Standard deviation of the phase error $\Delta\Phi$ as a function of the phase modulation depth $\delta$ for one (a) and two (b)		
Fig. 20:	signal periods processed	• •	50
Fig. 21:	(b) signal periods processed		51
Fig. 22:	and noise (index "n") induced signals		52
Fig. 23:			53
	tudes of the detected component with the frequency $2\omega$ for a noise frequency $2x\omega$ and for an integration over two signal periods		54
Fig. 24:			55
Fig. 25:			
	nent for n = 1024 data sampling points		56
Fig. 26:	Effect of random noise on the normalized amplitude		20
	e <sub>r</sub> of the detected periodic component for n = 1024 data sampling points		56

Fig. 27:	Effect of random noise on the periodic component with the frequency $2\omega$ as a function of the number	
Fig. 28:	n of data points per period processed	57
	for linearly polarized incident light; P = 45°; Pa-	
Fig. 29:	rameter: normalized AC amplitude e	59
- 562.	Ψ and Δ as functions of the normalized AC ampli-	
	tude e, and of the phase angle $\Phi$ for linearly polarized incident light and a polarizer azimuth $P = 45^{\circ}$	60
Fig. 30:	Rotating analyzer ellipsometry: Ellipsometric angles	00
	Ψ and Δ as functions of the normalized AC ampli-	
	tude e, and of the phase angle $\Phi$ for linearly polarized incident light and a polarizer azimuth $P = 15^{\circ}$	61
Fig. 31:	Rotating analyzer ellipsometry: Ellipsometric angles	
	$\Psi$ and $\Delta$ as functions of the normalized AC amplitude e, and of the phase angle $\Phi$ for circularly	
	polarized incident light	62
Fig. 32:	Rotating analyzer ellipsometry: Uncertainties $\delta\Psi$ (a), (b) and $\delta\Delta$ (c) of the ellipsometric angles for an	
	amplitude error $\Delta e/e = 0.01$ as a function of the	
	phase angle Φ for linearly polarized incident light	
	with P = 45° (a) and P = 15° (b), or for circularly polarized incident light (a); Parameter: normalized	
	AC amplitude e. The graphs for δΔ (c) apply to any	
T' 00	polarization of the incident beam	63
Fig. 33:	Rotating analyzer ellipsometry: Uncertainties $\delta\Psi$ (a), (b) and $\delta\Delta$ (c) of the ellipsometric angles for a	
	phase error $\Delta \Phi = 1^{\circ}$ as a function of the phase	
	angle $\Phi$ for linearly polarized incident light with P = $45^{\circ}$ (a) and P = $15^{\circ}$ (b), or for circularly polar-	
	= 45° (a) and P = 15° (b), or for circularly polarized incident light (a); Parameter: normalized AC	
	amplitude e. The graphs for $\delta\Delta$ (c) apply to any	
	polarization of the incident beam	65
Fig. 34:	Rotating analyzer ellipsometry: Uncertainties δΨ	
	(a), (b) and δΔ (c) of the ellipsometric angles for an	
	amplitude error $\Delta e/e = 0.01$ and a phase error $\Delta \Phi = 1^{\circ}$ as a function of the phase angle $\Phi$ for linearly	
	polarized incident light with P = 45° (a) and P =	
	15° (b), or for circularly polarized incident light	
	(a); Parameter: normalized AC amplitude e. The	
	graphs for $\delta\Delta$ (c) apply to any polarization of the	67
	incident beam	67

Fig. 35:	Substrate data: Influence of the substrate refractive index $(n_s)_c$ used for the calculation of film thicknesses and refractive indices on the relative error x of the computed film thickness (a), on the calculated film refractive index $(n_f)_c$ (b), and on the absolute error of the thicknesses of ultra-thin films (c).	71
Fig. 36:	Model for the analysis of an inhomogeneous inter- face layer between the substrate and a dielectric	
Fig. 37:	film	73
	substrate and an arbitrary film for the two models "a" and "b"	74
Fig. 38:	Variations of the real and imaginary parts of the refractive index of an inhomogeneous film over its	, ,
	thickness d; according to the models "a" and "b"	74
Fig. 39:	Inhomogeneous interface layer: Difference between the calculated film thickness d <sub>c</sub> and the actual distance z between the surfaces of the substrate and of the deposited ultra-thin SiO <sub>2</sub> film for various thicknesses d <sub>i</sub> of the inhomogeneous interface layer	
Fig. 40:	for the two models "a" (a) and "b" (b)	76
Fig. 41:	the calculated thickness $d_c$ (a) and refractive index $(n_f)_c$ (b) over the first ellipsometric order for the two models "a" and "b". Calculation based on the	78
Fig. A1:	actual substrate refractive index	79
	ellipsometer	82
rig. A2:	Data processing system of the high-speed rotating analyzer ellipsometer.	85